

**Search Notes**

Application No.

10/630,716

Examiner

Stephen W. Smoot

Applicant(s)

FUKUYAMA ET AL.

Art Unit

2813

**SEARCHED**

Class	Subclass	Date	Examiner
438	623	8/20/2004	SWS
438	624	6/20/2004	SWS
438	637	6/20/2004	SWS
438	638	6/20/2004	SWS
438	675	8/20/2004	SWS
438	763	8/20/2004	SWS
438	780	8/20/2004	SWS
257	635	8/20/2004	SWS
257	637	8/20/2004	SWS
257	642	8/20/2004	SWS
257	774	8/20/2004	SWS
257	775	8/20/2004	SWS
257	E23.145	8/20/2004	SWS
Updated	Above	2/3/2005	SWS

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: Low Dielectric Constant - Low k, Low Permittivity; Contact Hole, Opening Via; Interconnect - Trace, Line, Wiring;	8/20/2004	SWS
Interlayer, ILD, IMD - Organic, Porous Silica; Borderless Contact; Transistor - Source, Gate, Drain.	8/20/2004	SWS
Updated Above Search	2/3/2005	SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	8/20/2004 2-3-05	SWS SWS